

Electronic Supplementary Information

Ultrasensitive molecular sensing of few-layer niobium diselenide

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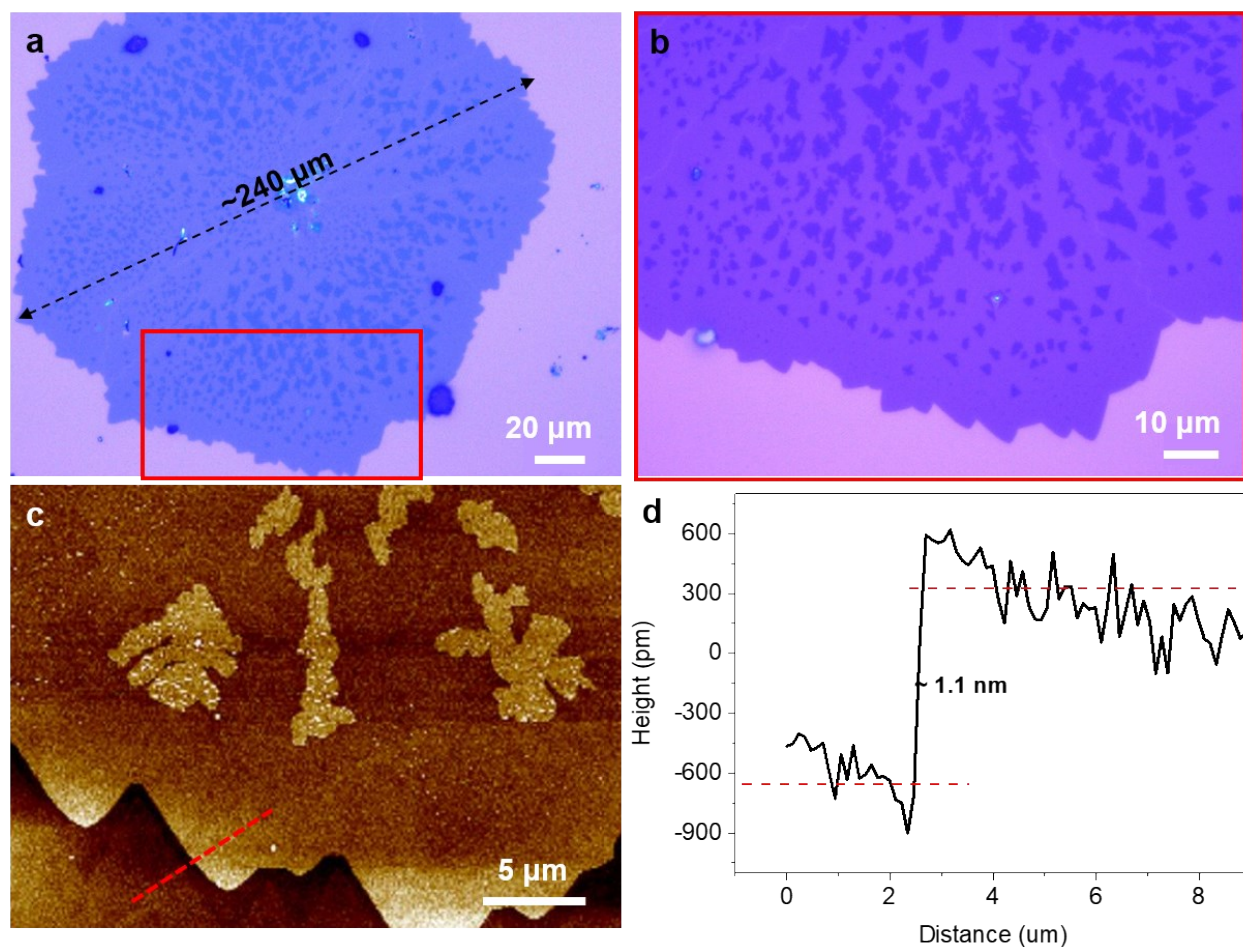


Fig. S1. (a, b) Typical optical images of as-grown large-area NbSe₂. (c) Atomic force microscope (AFM) image and (d) the corresponding height profile of as-grown NbSe₂. The small irregular areas on top are the second NbSe₂ layers.

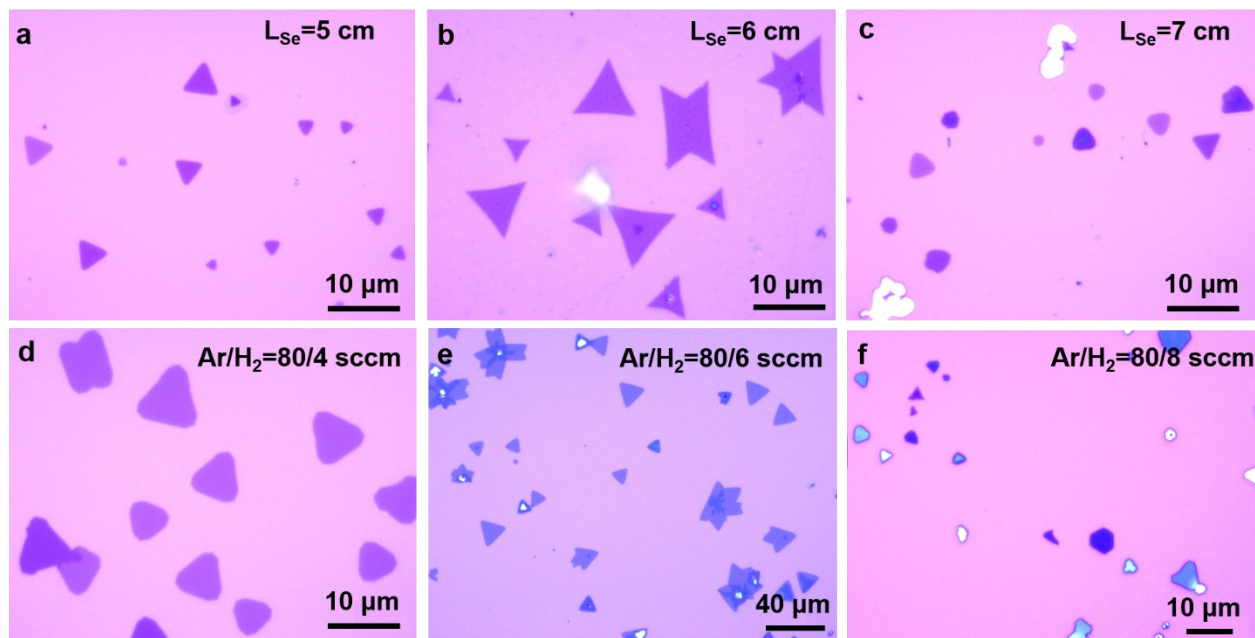


Fig. S2. Optical images of NbSe₂ flakes synthesized at different conditions: (a-c) at different L_{Se} values. Here L_{Se} denotes the distance of Se source from the left end of the furnace (as shown in Figure 1). (d-f) NbSe₂ flakes synthesized with different H₂ contents in the carrier gas (Ar/H₂ mixture). Here Ar/H₂=80/4 denotes that the Ar flow and H₂ flow are 80 sccm and 4 sccm, respectively. The others are named in the same rule.

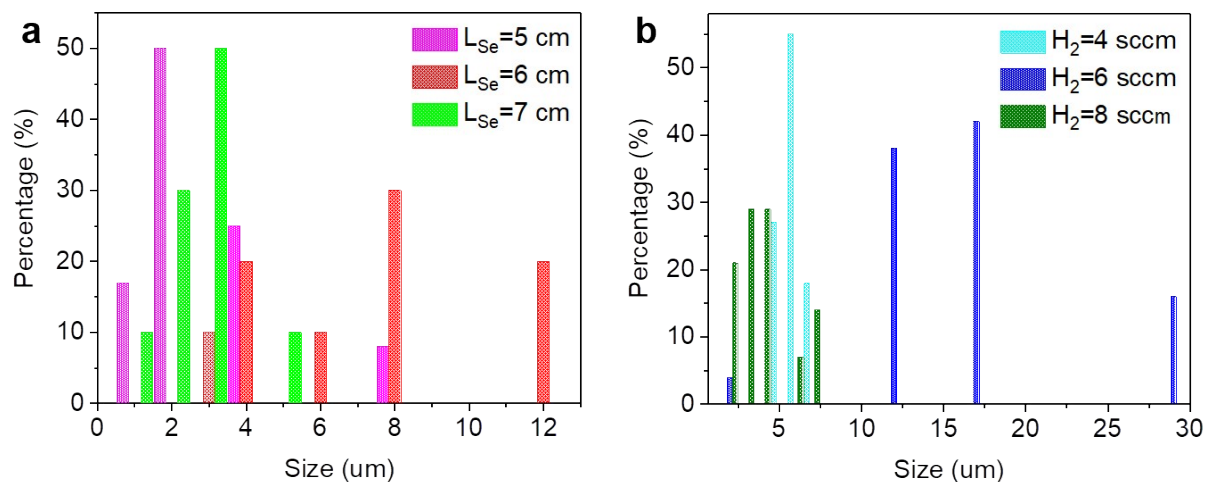


Fig. S3. Size distributions of as-grown NbSe₂ with different (a) L_{Se} values and (b) hydrogen flows.

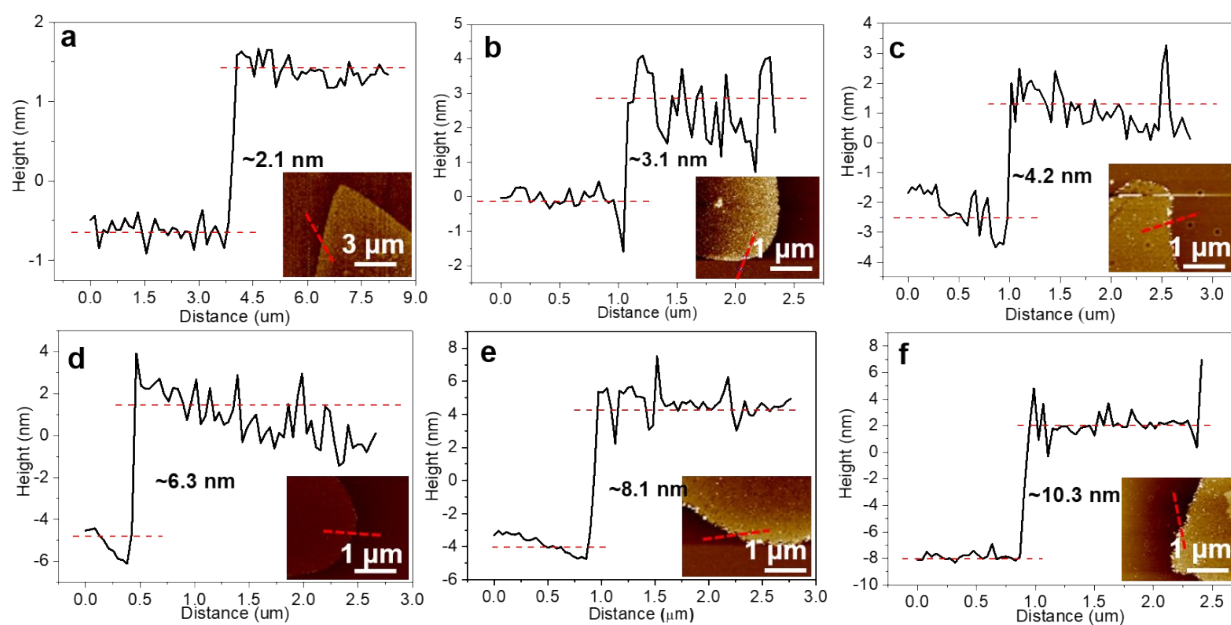


Fig. S4. AFM height profiles and the images (inset of each profile of each panel) of as-grown NbSe₂ with tunable thicknesses.

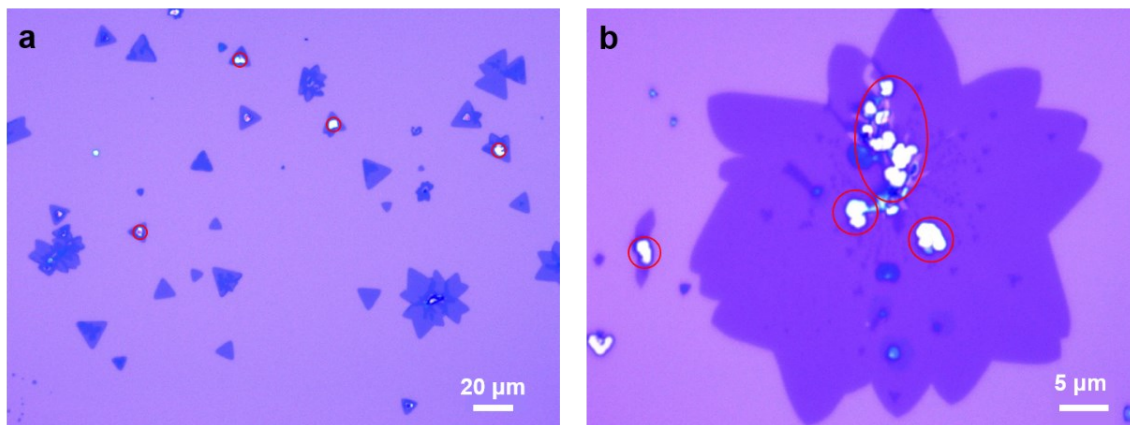


Fig. S5. Optical images showing the residual Nb₂O₅ particles on as-grown NbSe₂ flakes marked by red circles.

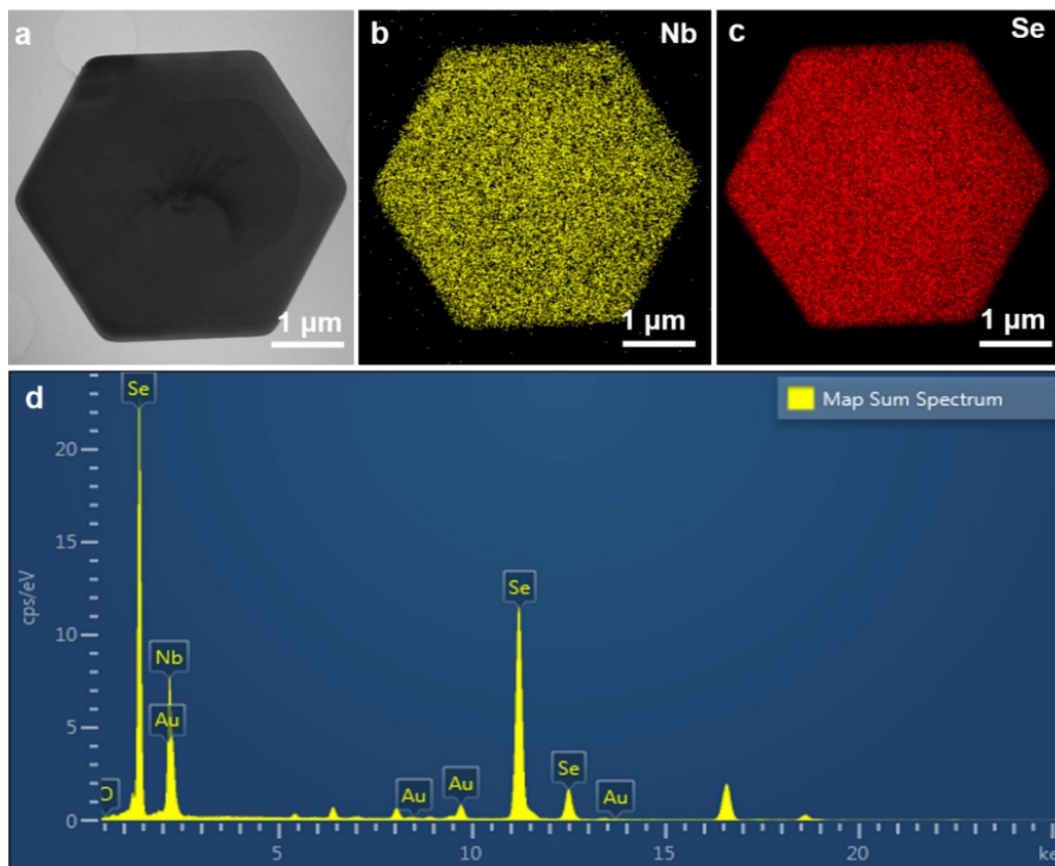


Fig. S6. Energy-dispersive X-ray spectrometer (EDS) elemental mapping of as-grown NbSe₂. (a) Bright field image of NbSe₂ on Au quantifoil grid collected in the scanning-transmission electron microscope (STEM) mode and the corresponding EDS mappings of (b) Nb and (c) Se, respectively. (d) EDS spectra of NbSe₂.

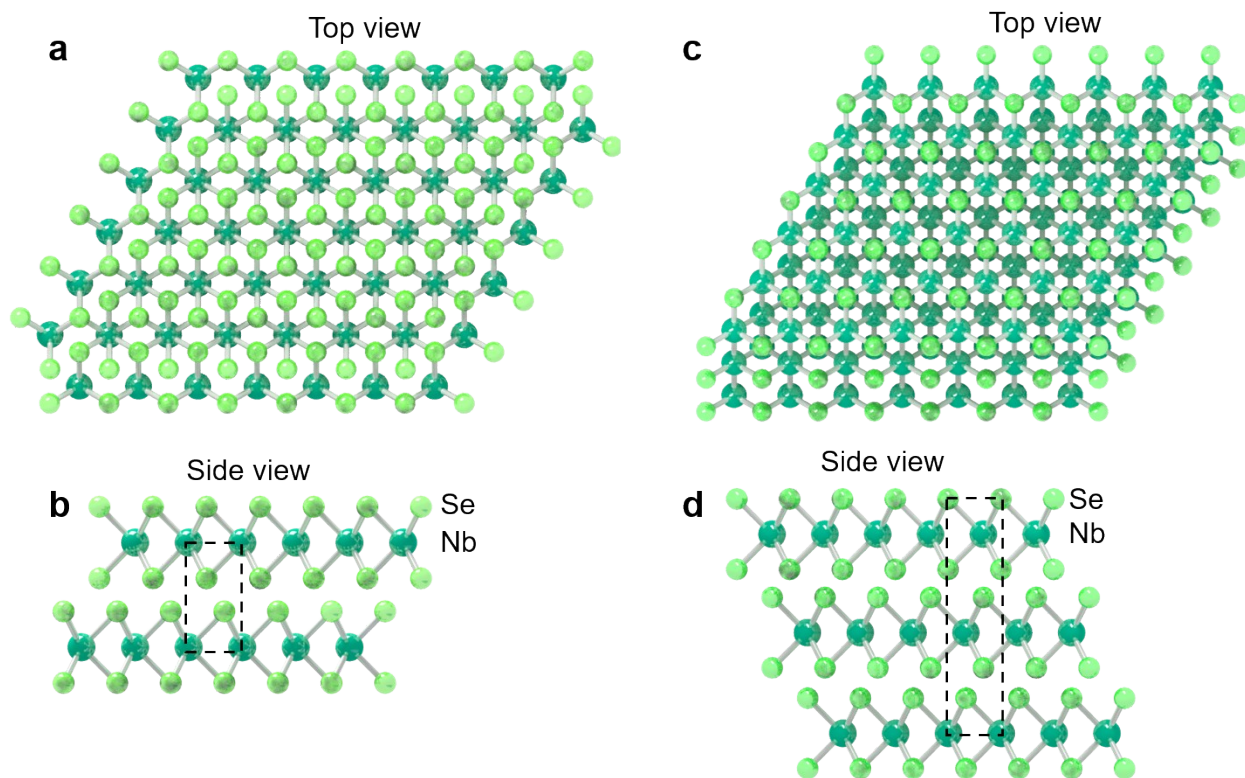


Fig. S7. Atomic structures of (a, b) $2H_a$ -NbSe₂ with A'B stacking mode and (c, d) 3R-NbSe₂ with AA stacking mode at top and side views.

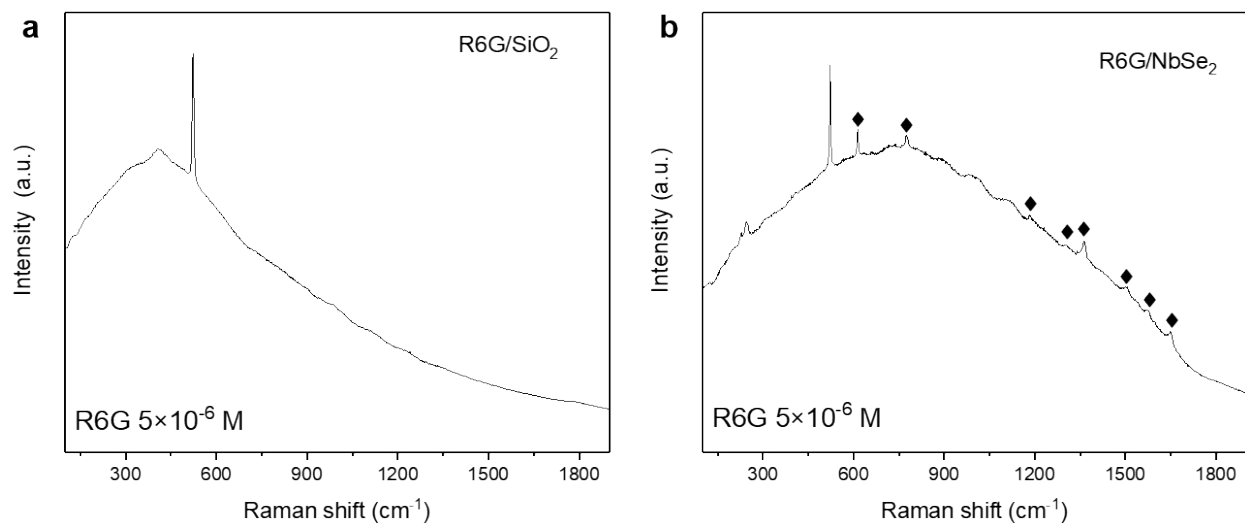


Fig. S8. Comparison of Raman spectra of R6G on bare SiO₂/Si and NbSe₂.

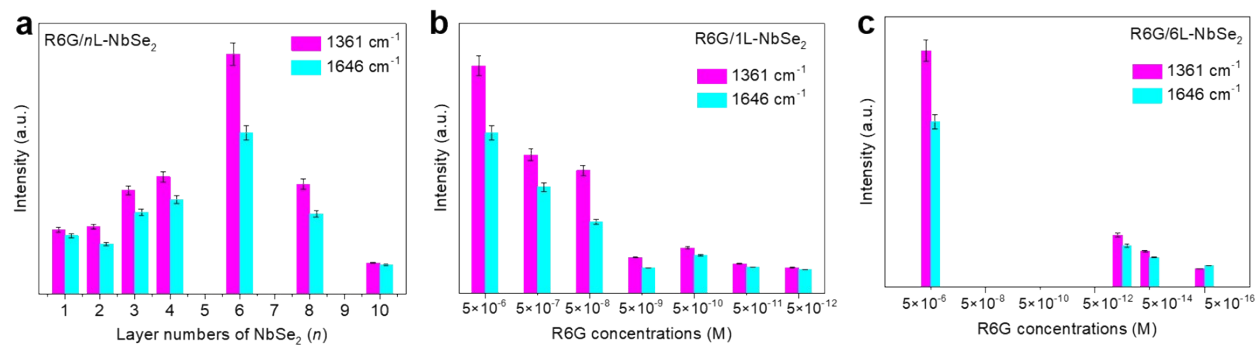


Fig. S9. (a) Raman intensities at 1361 and 1646 cm⁻¹ of R6G on NbSe₂ with different layers, (b, c) Raman intensities at 1361 and 1646 cm⁻¹ of R6G on (b) 1L-NbSe₂ and (c) 6L-NbSe₂ with different concentrations.

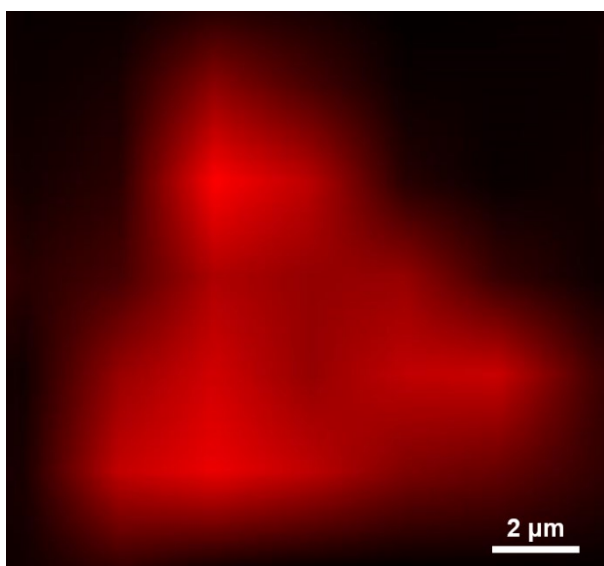


Fig. S10. Raman intensity mapping of R6G (5×10⁻⁶ M) at 1646 cm⁻¹ on NbSe₂.

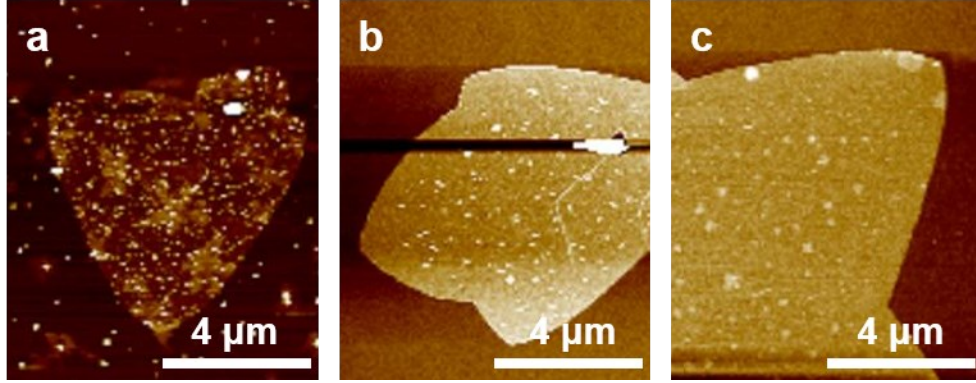


Fig. S11. AFM images of R6G on NbSe₂ with different concentrations: (a) 5×10^{-5} M, (b) 5×10^{-6} M and (c) 5×10^{-11} M.

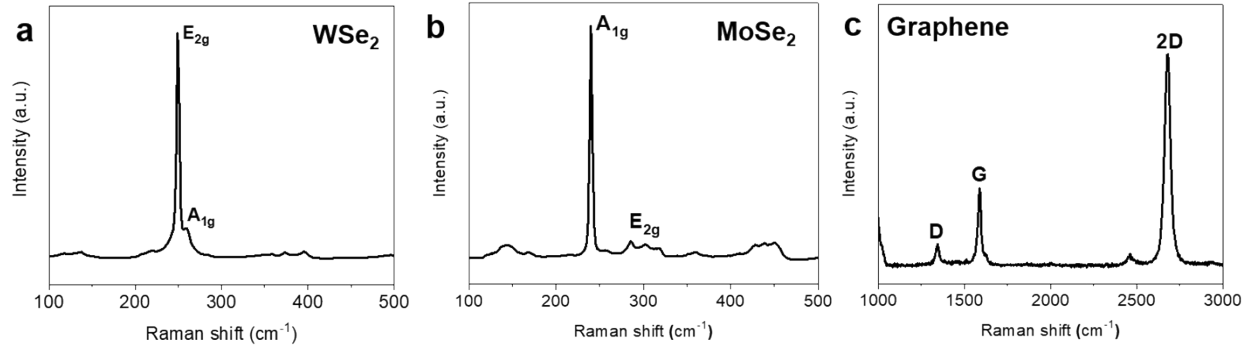


Fig. S12. Characterizations of different 2D materials grown by atmospheric pressure chemical vapor deposition (AP-CVD). Raman spectra of (a) WSe₂, (b) MoSe₂ and (c) graphene.

Table S1. Comparison of molecular sensing properties of different materials as substrates

Types	Substrates	Probe molecules	Limits of detection/M	Laser excitation wavelength/nm	Data source
Non-noble metal-based materials	NbSe ₂	R6G	5×10⁻¹⁶	532	This work
	NbS ₂	MeB	1×10 ⁻¹⁴	633	1
	1T'-WTe ₂	R6G	4×10 ⁻¹⁴	532	2
	1T'-MoTe ₂	R6G	4×10 ⁻¹³	532	2
	MoS ₂ /graphene	R6G	5×10 ⁻¹²	532	3
	1T-MoS ₂	R6G	1×10 ⁻⁹	532	4
	Few-layer MoS ₂	R6G	1×10 ⁻⁹	532	5
	W ₁₈ O ₄₉ /MoS ₂	R6G	1×10 ⁻⁹	532	6
	1T'-ReS ₂	R6G	1×10 ⁻⁹	532	7
	NG ^a	R6G	1×10 ⁻⁹	514	8
	MnPS _{2.4} Se _{0.6}	R6G	1×10 ⁻⁸	532	9
	1T-MoSe ₂	R6G	1×10 ⁻⁸	532	10
	Oxygen-incorporated MoS ₂	R6G	1×10 ⁻⁷	532	11
	2H-MoS ₂	R6G	5×10 ⁻⁶	532	3
Noble-metal-based materials	Au/h-BN/Ag	R6G	1×10 ⁻¹²	514	12
	Ag NP-VE/OCT ^b	R6G	1×10 ⁻⁹	633	13
	Au@Ag/3D-Si	R6G	1×10 ⁻⁸	532	14

Note: ^{a)} NG: nitrogen-doped graphene; ^{b)} Ag NP-VE/OCT: Ag nanoparticles-vitamin E-1-octanol.

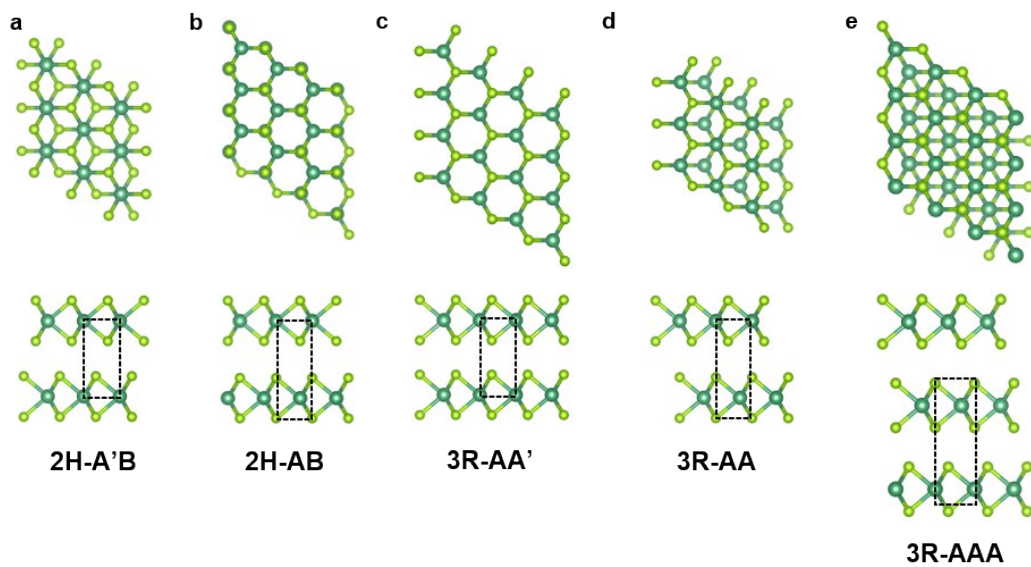


Fig. S13. Structural polytypes of few-layer NbSe₂ with different stacking modes. (a) 2H-A'B. (b) 2H-AB. (c) 3R-AA' phase. (d) 3R-AA. (e) 3R-AAA.

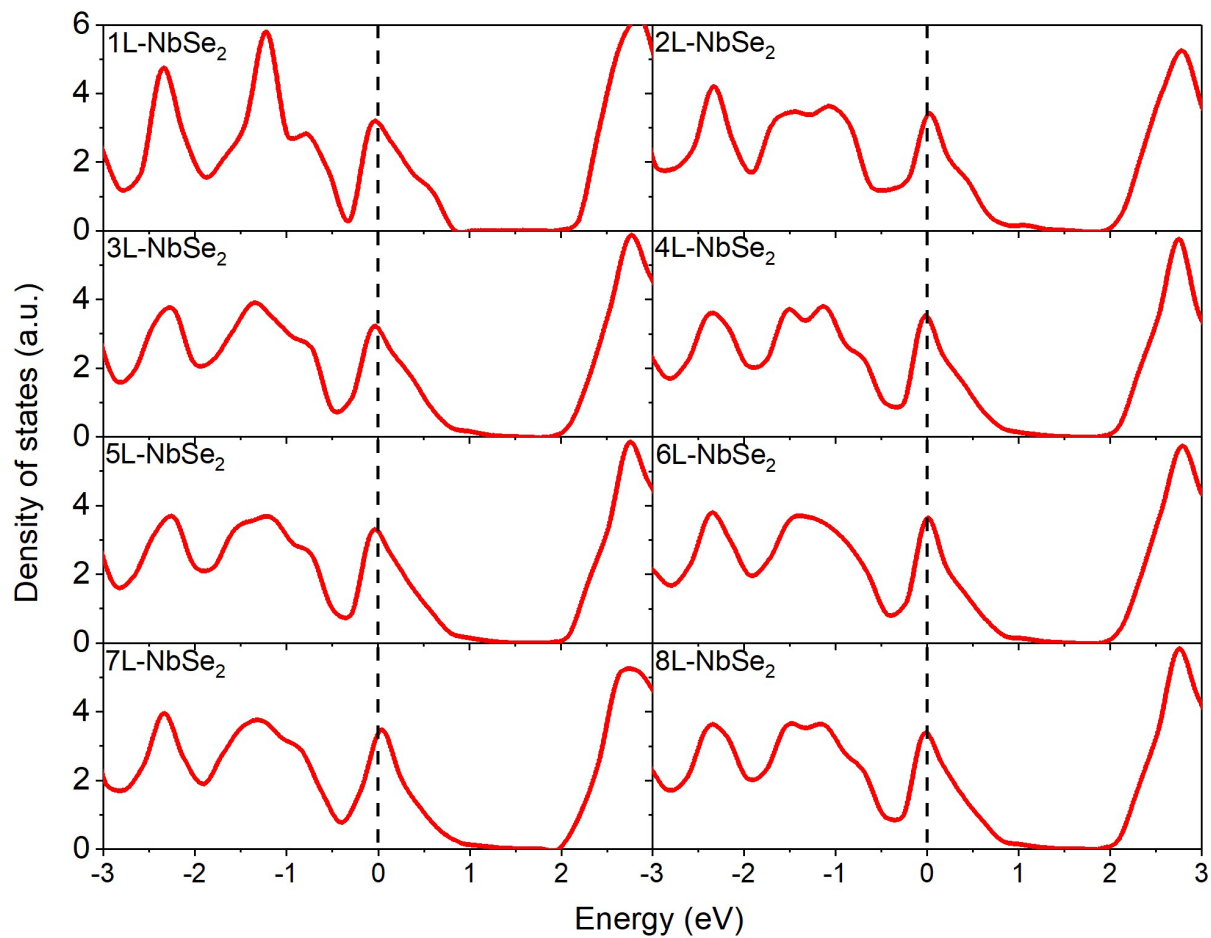


Fig. S14. Density of states (DOS) of the outmost layer NbSe₂ with 2H_a-A'B stacking mode.

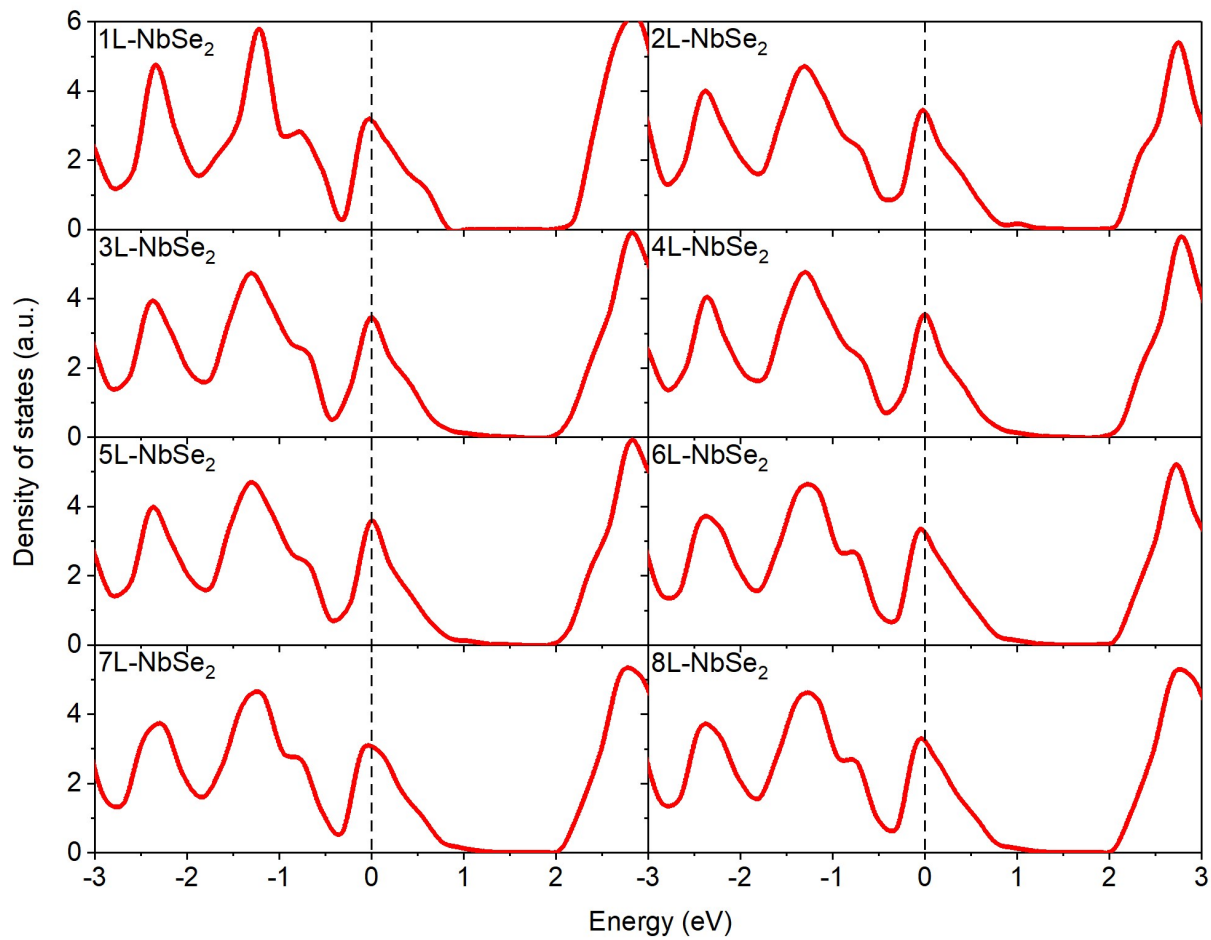


Fig. S15. DOS of the outmost layer of NbSe₂ with 3R-AA stacking mode.

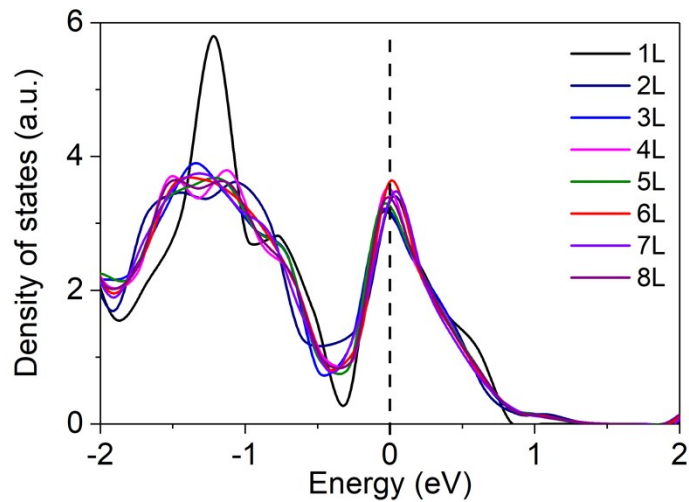


Fig. S16. DOS of the outmost layer of NbSe₂ with 2H_A-A'B stacking modes.

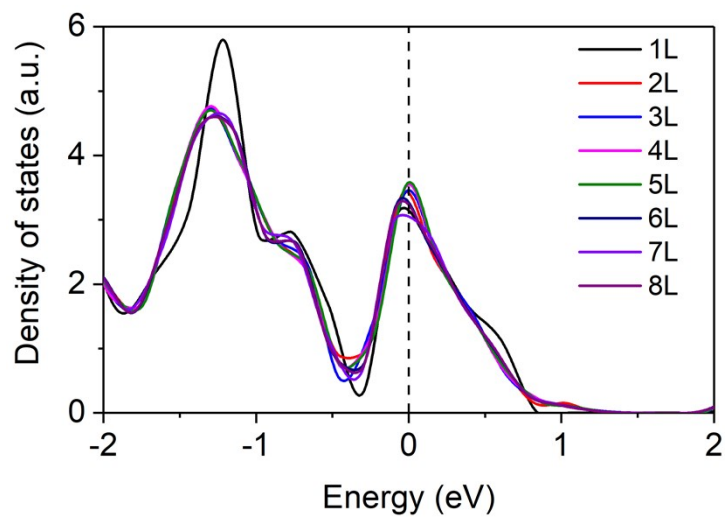


Fig. S17. DOS of the outmost layer of NbSe₂ with 3R-AA stacking modes.

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